

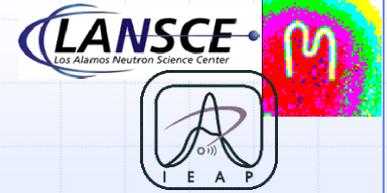
# Measurement of the Ionizing Energy Depositions after Fast Neutron Interactions in Silicon

**B. Bergmann**<sup>a)</sup>, I. Caicedo<sup>a)</sup>, E. Fröjdh<sup>c)</sup>, J. Kirstead<sup>b)</sup>, S. Pospisil<sup>a)</sup>, H. Takai<sup>b)</sup>, D. Turecek<sup>a)</sup>

a) Institute for Experimental and Applied Physics, Czech Technical University in Prague, Horská 22/3a, 128 00 Praha 3

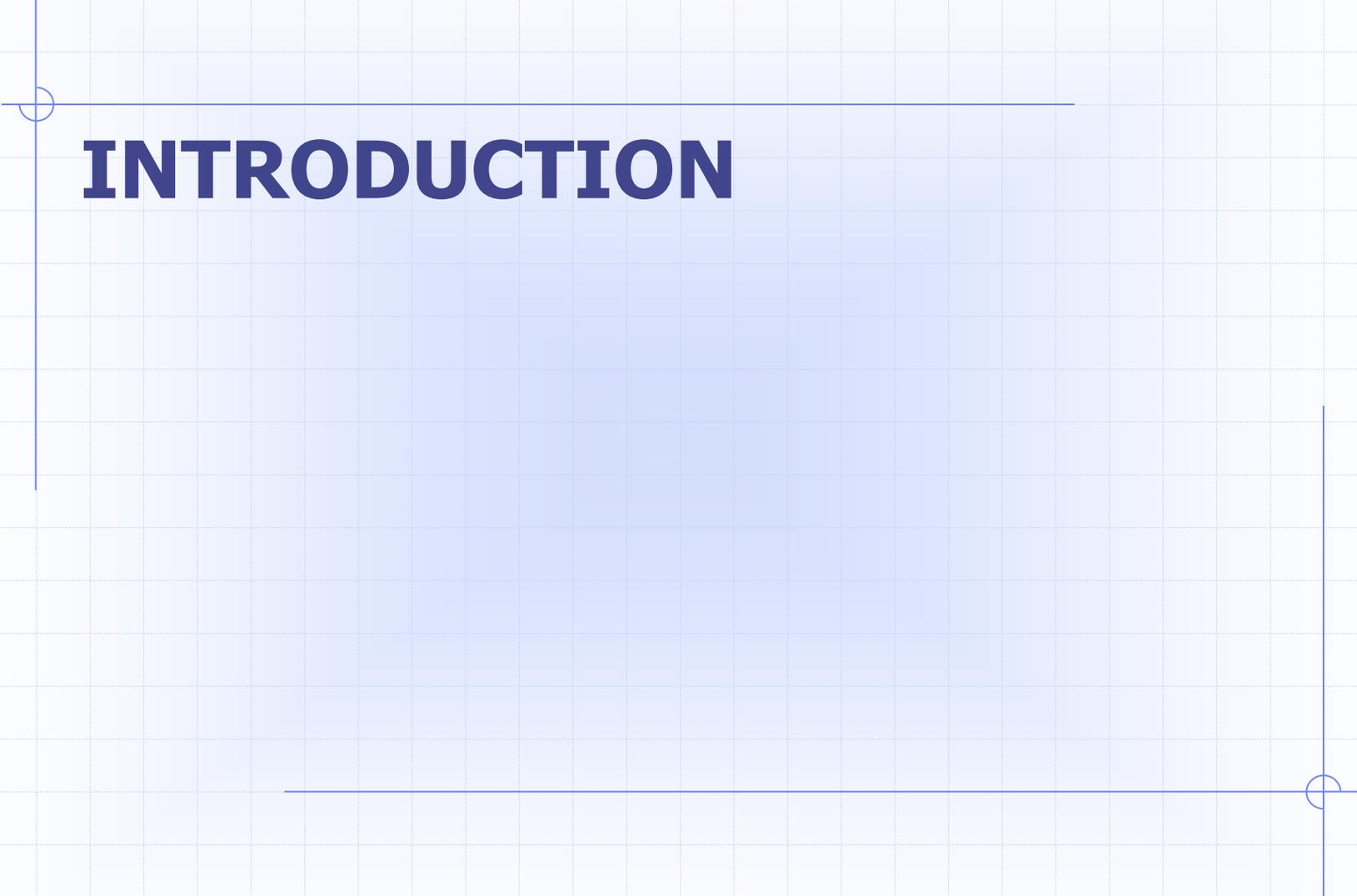
b) Brookhaven National Laboratory, P.O. Box 5000, Upton, NY 11973-5000, United States

c) CERN, CH-1211 Geneva 23, Switzerland



# Outline

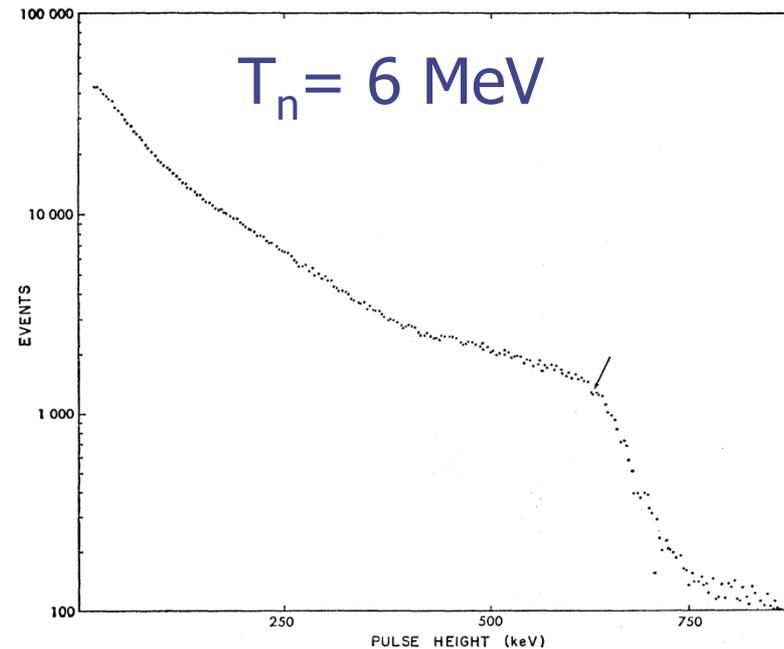
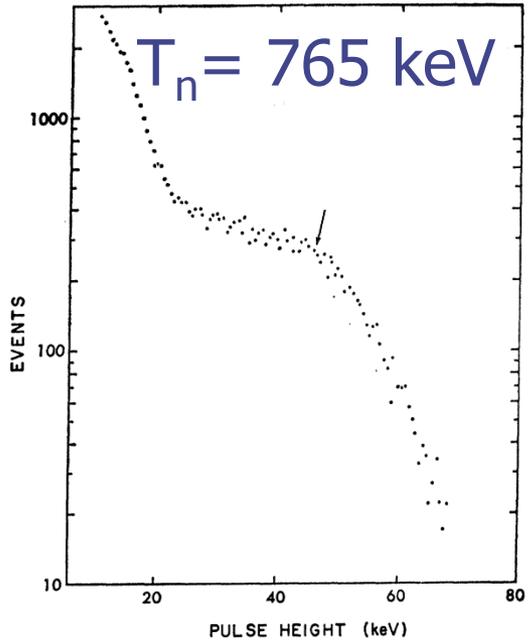
- ❑ Introduction
- ❑ Experimental setup and methods of data evaluation
- ❑ Results

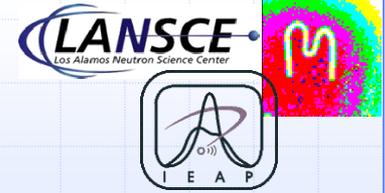


# INTRODUCTION

# Measurement of ionizing energy losses after monoenergetic neutron impact

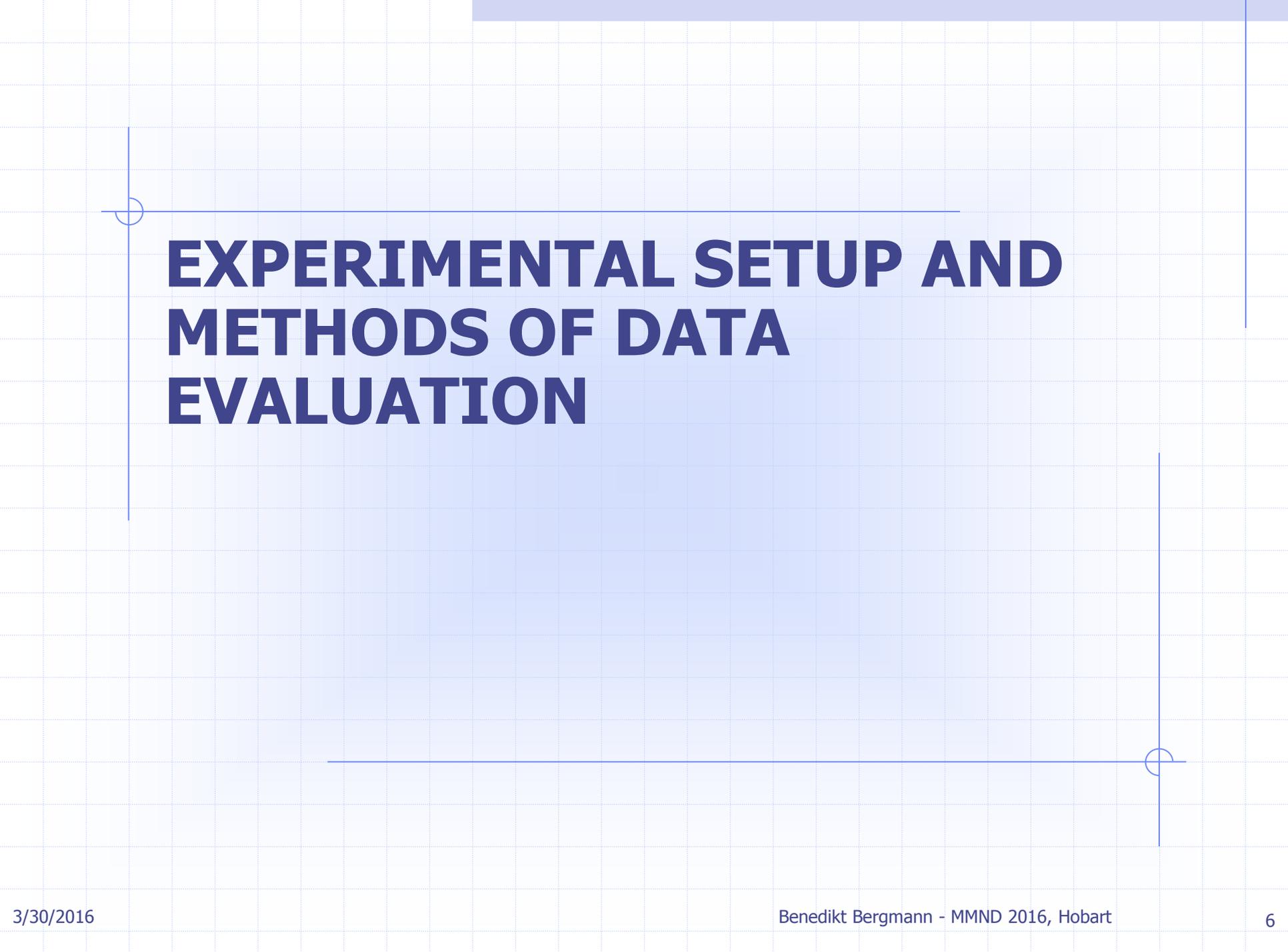
- Sattler, 1965:  
 “Ionization produced by energetic silicon atoms within a silicon lattice”  
 (Phys. Rev. Vol 138, Vol. 6 A)



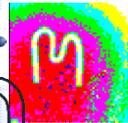


# Radiation damage in silicon

- ❑ Radiation damage affects performance of detectors and/or electronic circuits
  
- ❑ Permanent damage (changes in sensor material):
  - Displacement of silicon atoms within the lattice (non-ionizing energy depositions)
    - Increases leakage current
    - Decreases charge collection efficiencies
  
- ❑ Single Event Effects (changes in logic state of device):
  - High local charge deposition (ionizing energy losses)
    - Examples: SEU, MBU, ...



# **EXPERIMENTAL SETUP AND METHODS OF DATA EVALUATION**



# Timepix Detectors

- Timepix detectors
  - Hybrid pixel detectors
  - Developed at CERN
  - 256 x 256 pixels
  - Pixel pitch: 55 $\mu$ m
  - Silicon sensor layer flip-chip bump bonded to the ASIC

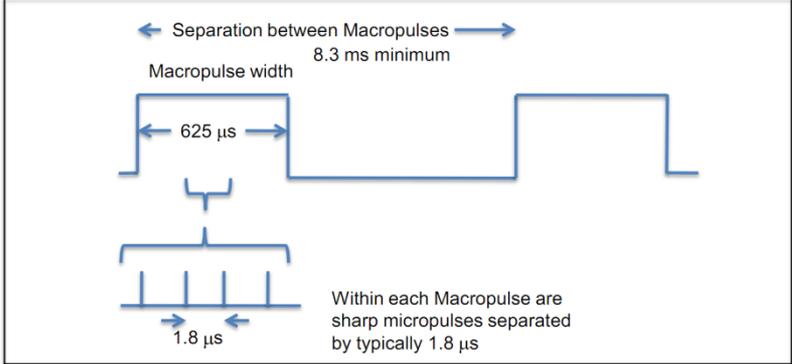
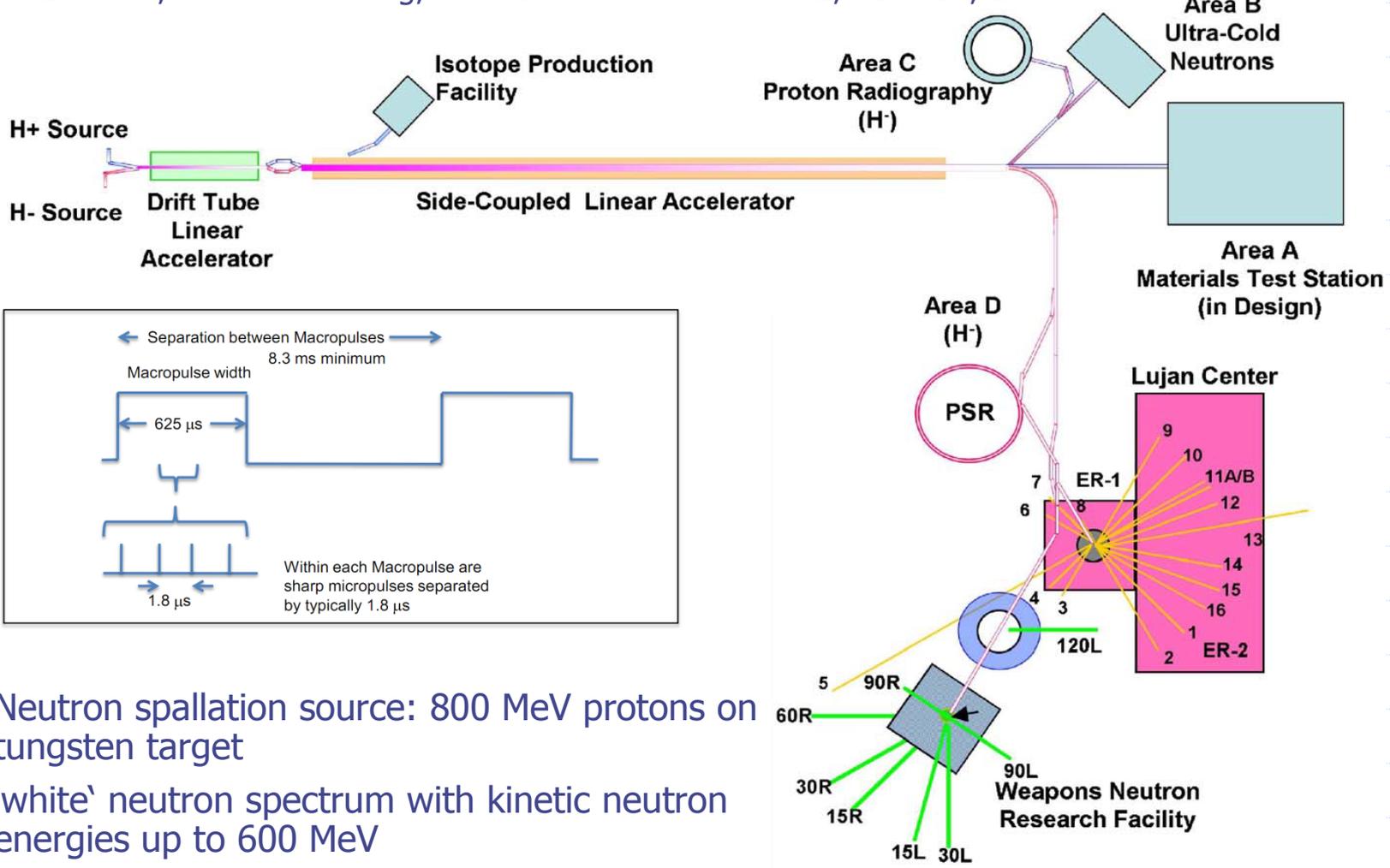


Timepix3 CERN chip board

- Timepix 3:
  - Thickness: 300 $\mu$ m
  - Depletion voltage: 90V
  - Data driven readout (Maximal count rate 40 Mpix/s)
  - Measurement of energy **and** time, simultaneously (time resolution 1.56 ns)
  - Threshold set to 5 keV (down to  $\sim$ 2 keV possible)

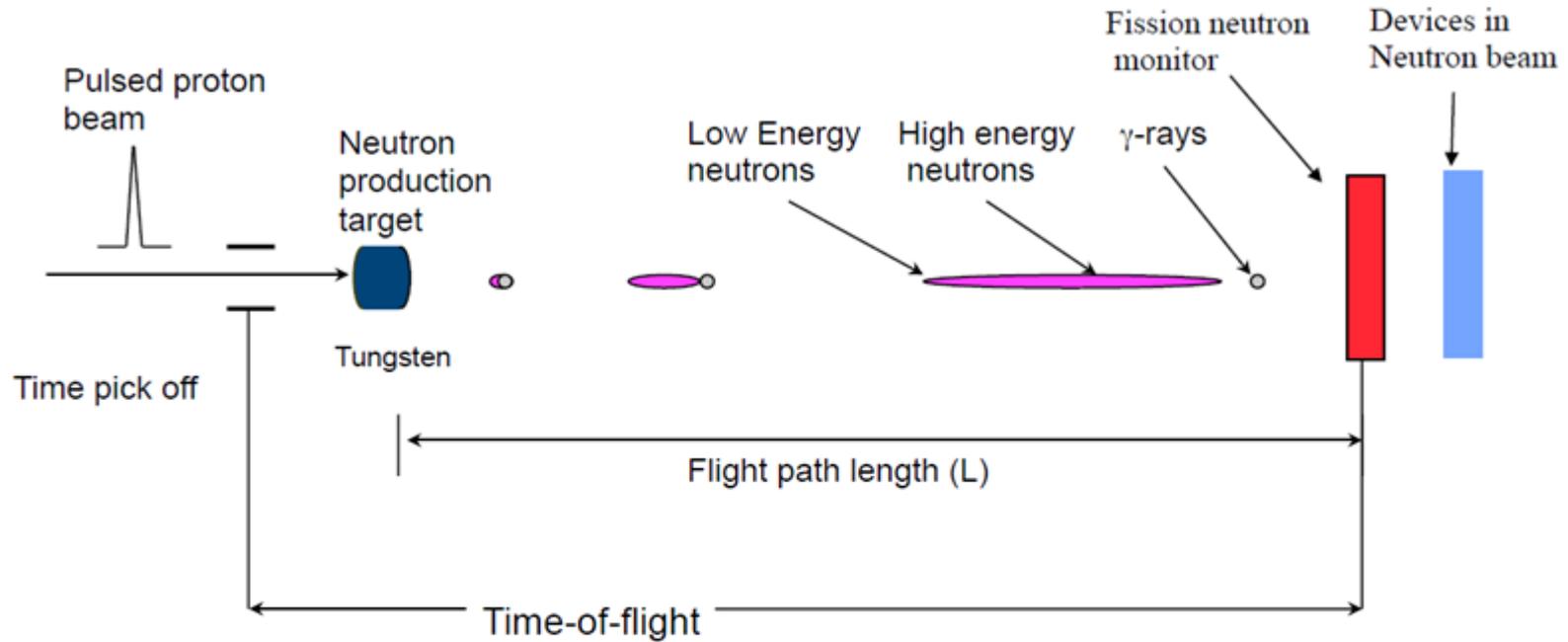
# Los Alamos Neutron Science Center (LANSCCE)

P. W. Lisowski, K. F. Schoenberg, Nucl. Instr. and Meth. A 562, 910-914, 2006



- Neutron spallation source: 800 MeV protons on tungsten target
- 'white' neutron spectrum with kinetic neutron energies up to 600 MeV

# Time-of-Flight technique



$$\text{Neutron TOF} = \frac{72.3L}{\sqrt{E_n}} \quad (\text{non-relativistic})$$

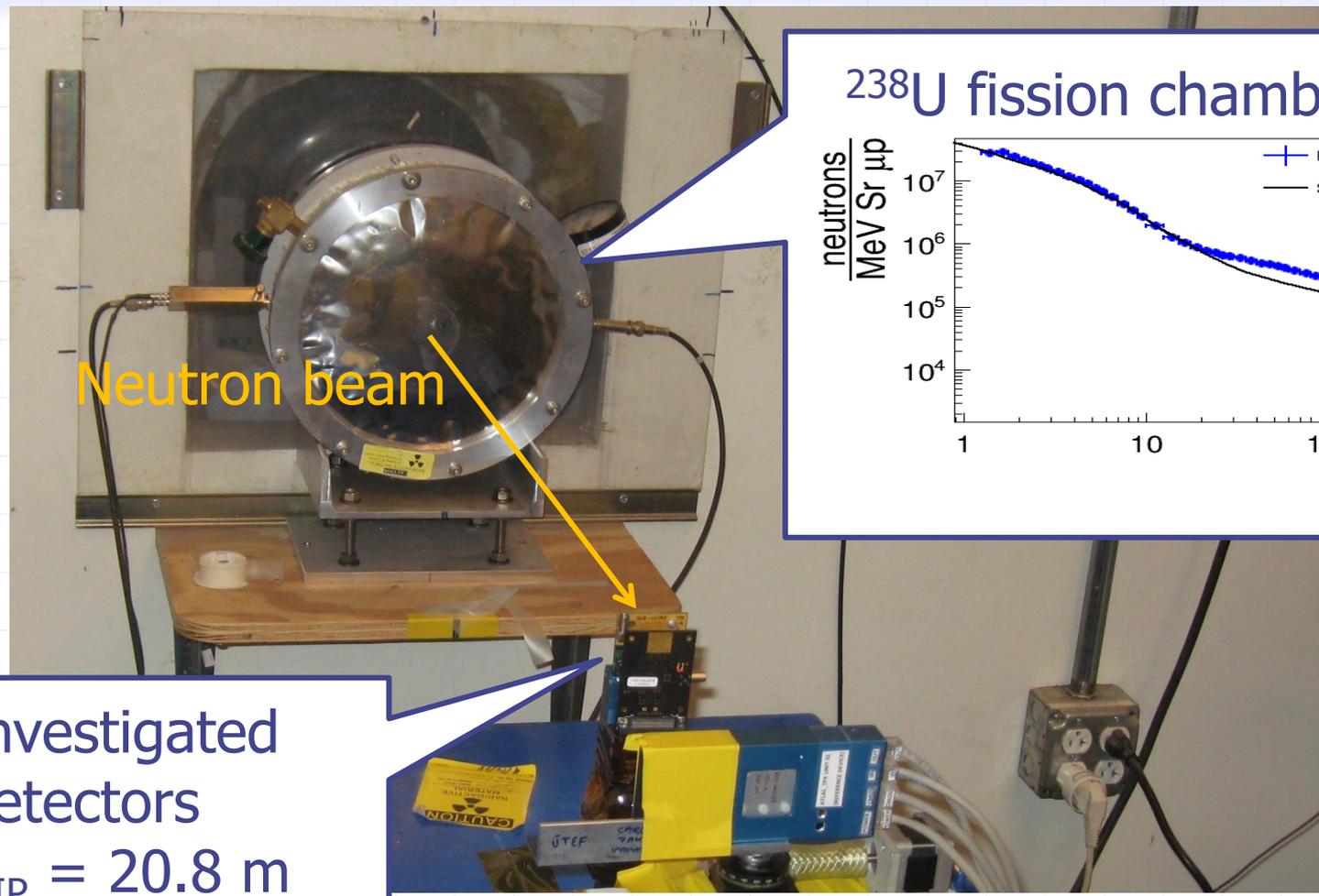
$$\gamma\text{-ray TOF} = \frac{L}{c} \quad c \text{ is velocity of light}$$

Example:  $L = 20\text{m}$   $E_n = 1 \text{ MeV}$   
 $\text{TOF}_n = 1.5 \mu\text{s}$   
 $\text{TOF}_\gamma = 67 \text{ ns}$

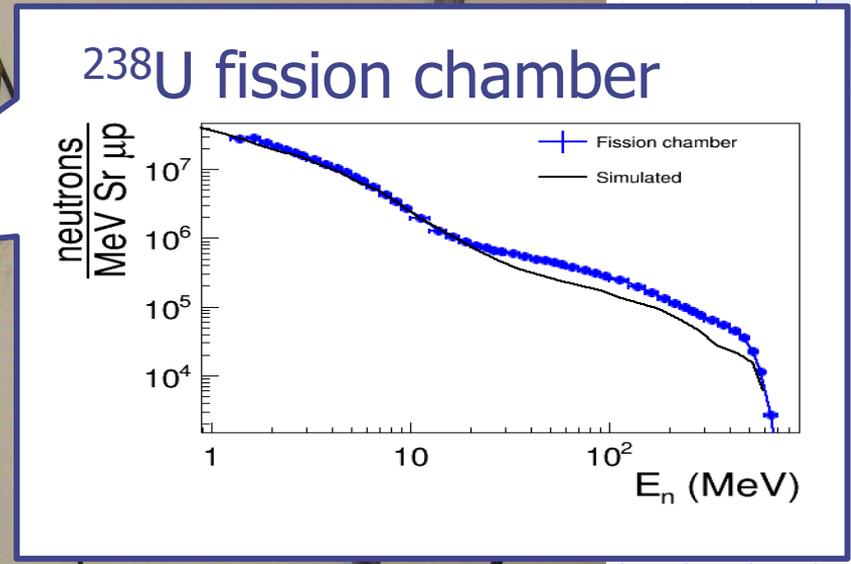
$E_n = 100 \text{ MeV}$   
 $\text{TOF}_n = 150 \text{ ns}$

# Experimental setup and neutron energy spectrum

Institute of Experimental and Applied Physics  
 Czech Technical University in Prague



Neutron beam

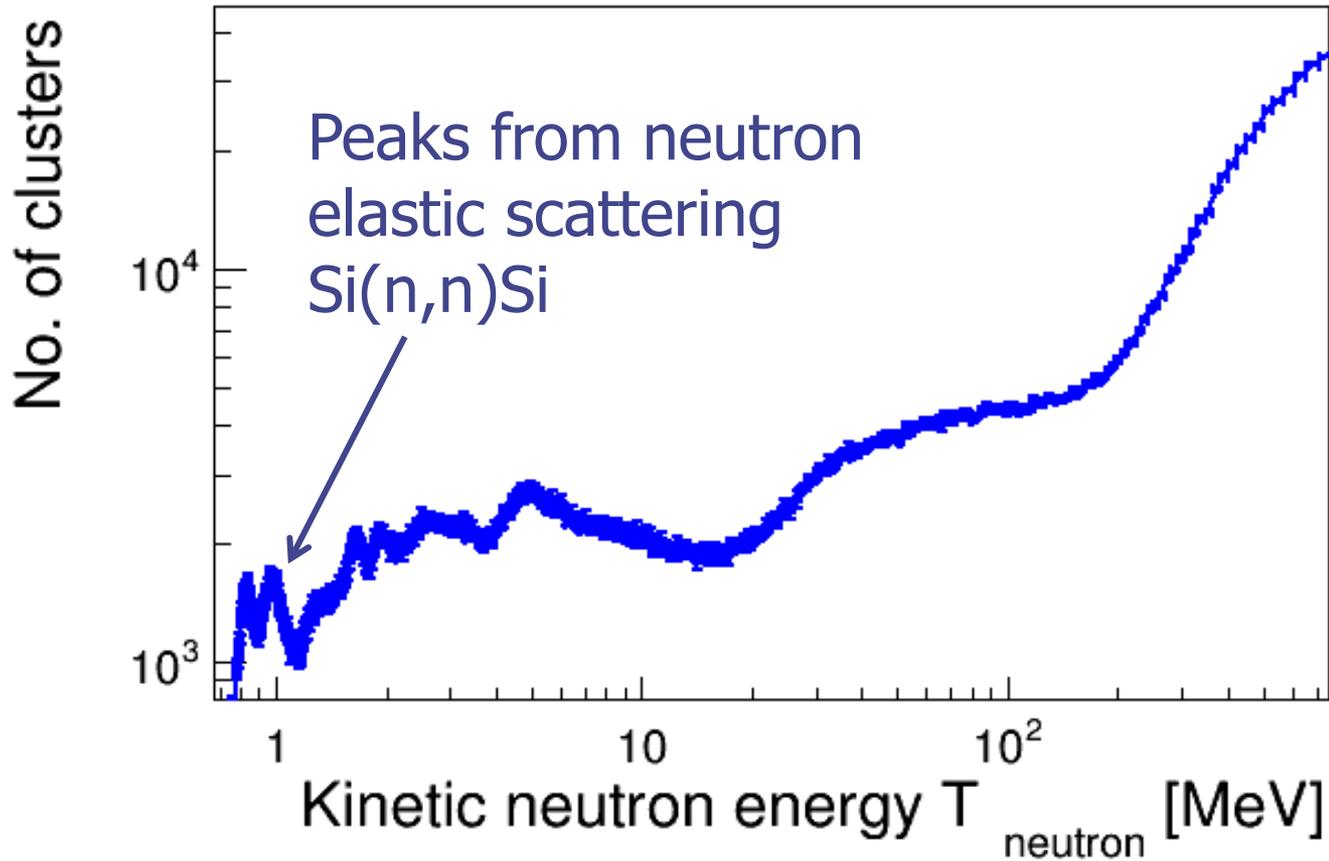


Investigated  
 detectors  
 $d_{IP} = 20.8 \text{ m}$

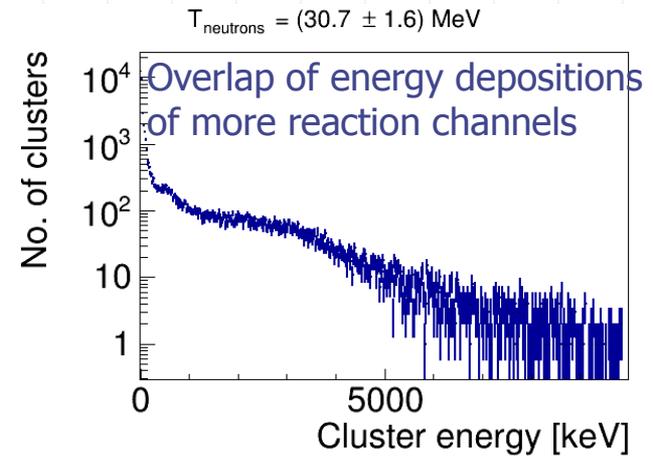
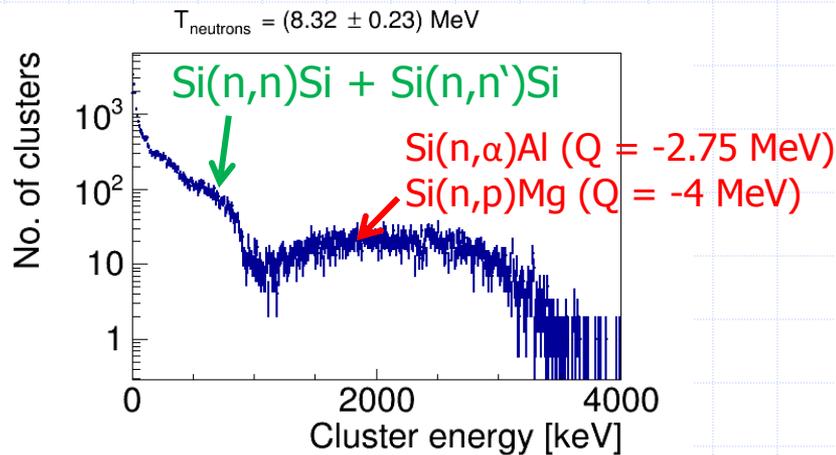
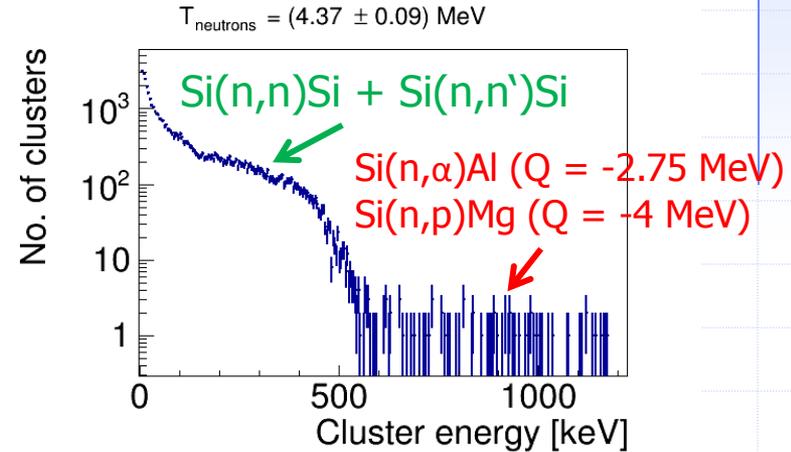
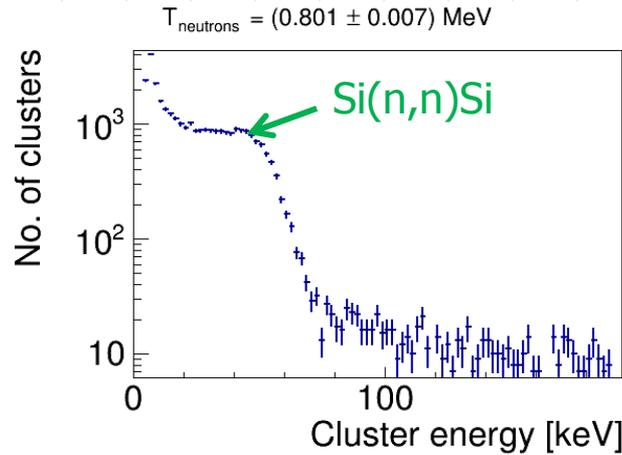


# RESULTS

# Measured neutron kinetic energy spectrum



# Examples of energy deposition spectra for selected neutron energy intervals



# Edges of energy depositions of silicon recoils from neutron elastic scattering

- Energy determination by fitting:

$$f(E) = \frac{A}{\exp\left(\frac{E-E_{edge}}{D}\right)+1} + B + C \cdot E$$

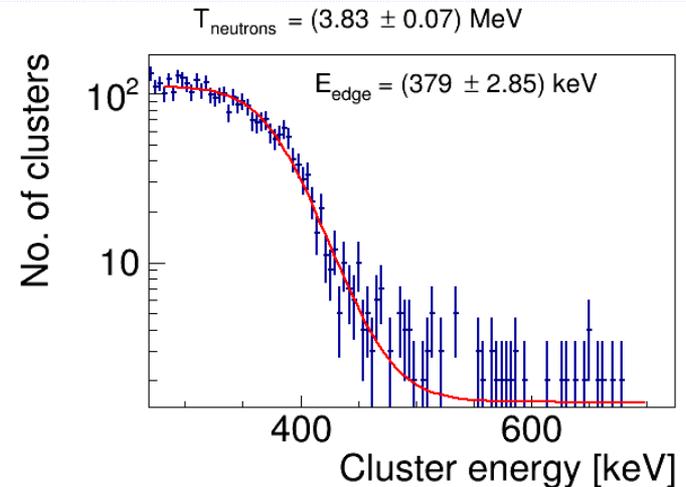
- Max. energy transfer to the silicon in elastic scattering:

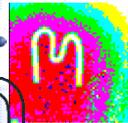
$$T_{Si,max} = \frac{4M_{Si}m_n}{(M_{Si} + m_n)^2} T_n = 0.133 \cdot T_n$$

→ Energy goes partly into displacement  $E_{NIEL}$  (NIEL) and ionization  $E_{ion}$ .

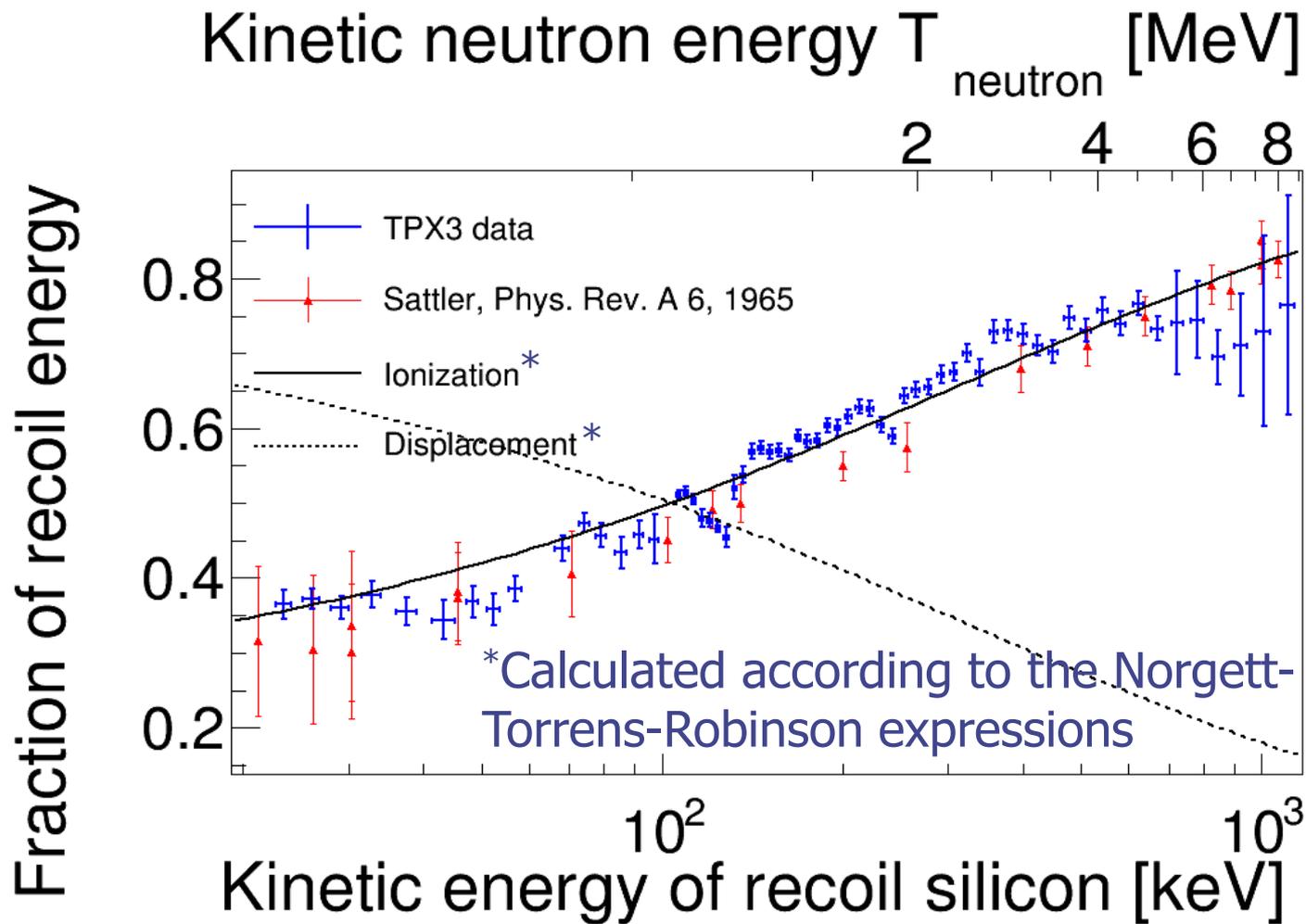
- Energy measured:  $E_{edge} = E_{ion}$ . (ionizing energy deposition)

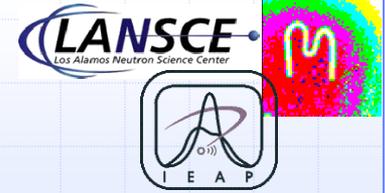
→ Fraction of ionizing energy losses:  $f_{meas,ion} = \frac{E_{edge}}{T_{Si,max}} = \frac{E_{edge}}{0.133 \cdot T_n}$





# Neutron scattering: Losses by ionization vs. losses due to displacement





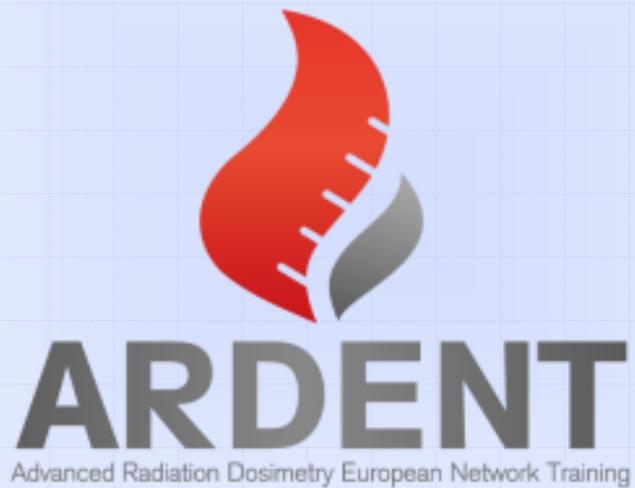
# Conclusion

- ❑ Example spectra of ionizing energy depositions of charged products after fast neutron impact were presented
- ❑ By spectrum analysis the competition of ionizing versus non ionizing energy losses was studied
- ❑ The results closely agreed with the calculations of Norgett-Torrens-Robinson and a previous measurement by Sattler

## Impact:

- ❑ Knowledge of ionizing energy depositions essential for single event effect estimation/simulations
- ❑ Knowledge of non ionizing energy depositions necessary for understanding permanent radiation damage

**Thank you for your attention!**



# Primary knock-on atoms and cascades of defects

1. Creation of primary knock-on silicon atom (PKA) in neutron elastic scattering

- Recoil silicon energy:  $T_{Si} = \frac{4M_{Si}M_n}{(M_{Si}+M_n)^2} \cdot (1 - \cos(\theta)) \cdot T_n$

2. PKA loses its energy by

- displacement of atoms from their lattice sites (NIEL) – cascade of displaced atoms, displacement damage
- ionization of atoms in the lattice (IEL)

- Competition of NIEL vs. IEL losses theoretically described by

$$f_{\text{NIEL}} = \frac{E_{\text{de}}}{E_{\text{Si}}} = \frac{1}{1+k \cdot g(\epsilon)} \quad \text{and} \quad f_{\text{ion}} = \frac{k \cdot g(\epsilon)}{1+k \cdot g(\epsilon)}$$

With  $k = 0.1462$ ,  $\epsilon = 1.014 \cdot 10^{-2} Z_{\text{Si}}^{1/7} \cdot E_{\text{Si}} = 2.147 \cdot 10^{-5} E_{\text{Si}}$  and  $g(\epsilon) = 3.4008 \cdot \epsilon^{1/6} + 0.40244 \cdot \epsilon^{3/4} + \epsilon$

# (Quasi-)monochromatic neutrons by means of ToF assignment

- Relative energy resolution as a function of neutron kinetic energy (assuming time resolution of 25 ns)

